

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application No.	10/623,482
	Filing Date	July 18, 2003
	First Named Inventor	Michael A. Todd
	Art Unit	2812
(Multiple sheets used when necessary)	Examiner	Ron Everett Pompey
SHEET 1 OF 1	Attorney Docket No.	ASMEX.376A

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
	1	4,720,395	01-19-1988	Foster	
	2	7,125,582	10-24-2006	McSwiney <i>et al.</i>	
	3	7,172,792	02-06-2007	Wang <i>et al.</i>	
	4	7,192,626	03-20-2007	Dussarrat <i>et al.</i>	
	5	2004/0096582 A1	05-20-2004	Wang <i>et al.</i>	
	6	2005/0080286 A1	04-14-2005	Wang <i>et al.</i>	
	7	2006/0084283 A1	04-20-2006	Paranjpe <i>et al.</i>	

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T ¹

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹
	8	ISHIHARA et al., "Low-temperature chemical-vapor-deposition of silicon-nitride from tetra-silane and hydrogen azide," <i>Materials Research Society Symposium Proceedings</i> , Volume 284, p. 3-8 (1993)	
	9	KANOH et al., "Low-temperature chemical-vapor-deposition of silicon nitride," <i>Journal de Physique IV</i> , Volume 2, p. C2-831-C2-837 (1991)	
	10	YEH et al., "Low-temperature chemical-vapor-deposition of silicon-nitride film from hexachloro-disilane and hydrazine," <i>Jpn. J. Appl. Phys.</i> Volume 35, Part 1, No. 2B, p. 1509-1512 (February 1996)	

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Examiner Signature	Date Considered
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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